

Norbornene-Carbon Monoxide Copolymerization & Dissolution Inhibitor Study

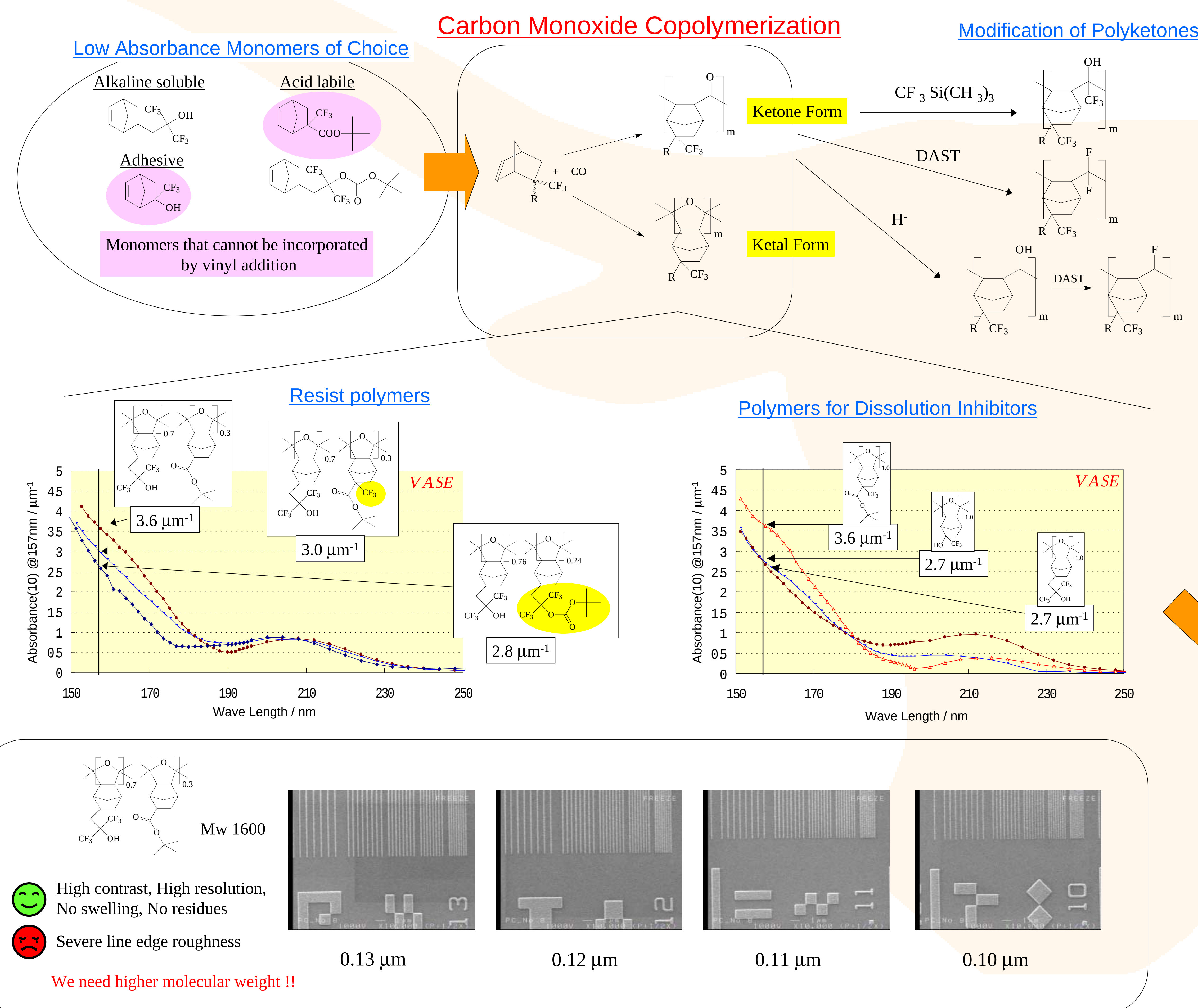
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Introduction:

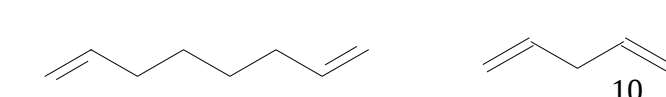
Several approaches have been investigated for polymerizing norbornene derivatives as 157 nm photoresist as these derivatives provide good etch-resistance properties. Carbon monoxide copolymerization is one of those approaches. This polymerization can provide two forms, ketal form and ketone form. Ketone form was explored to modify the ketone. However, the reactions were not successful. In this presentation, we show the carbon monoxide copolymerization in ketal form as a platform of 157 nm photoresist. We also show dissolution inhibitor study of the polymers including small molecules.

Dissolution Inhibitor Study



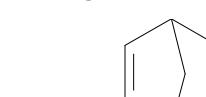
Addition of Cross Linker to Raise Mw

Terminal Olefins



No cross linking
Too little cross linking

Cyclic Diene



Hard to control Mw
Too much cross linking

Linked norbornene



Mw 6000
Just Right! 😊

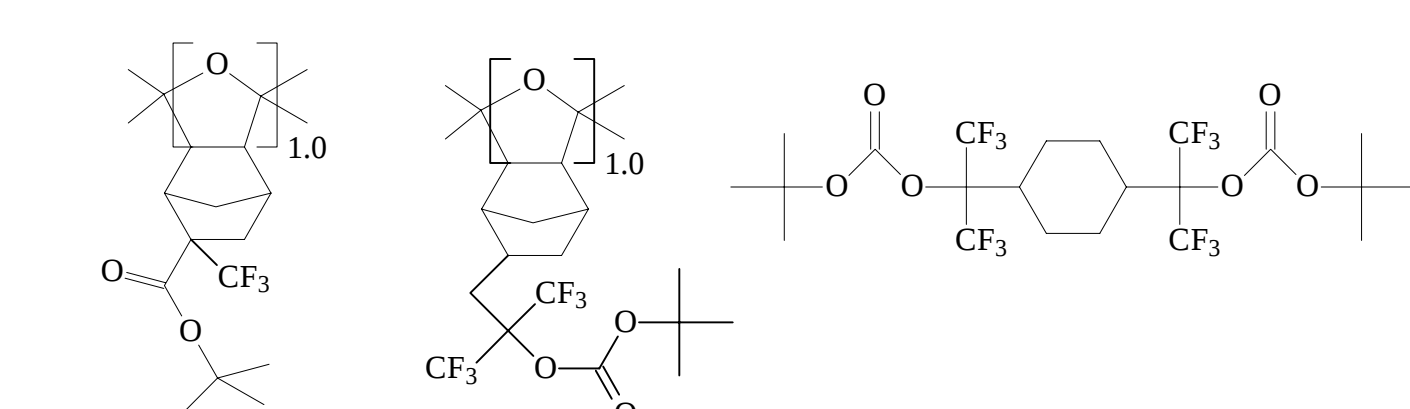
Future Work

- Scale up higher Mw polymers for imaging.
- Synthesize more transparent cross linkers.
- Continue imaging work.
- Explore utility as dissolution inhibitors.

Future Work

- Synthesize and test 1,3-HFAB derivatives
- Explore other dissolution inhibitor structures.

- Test CO-copolymers and HFAB derivatives for imaging as DIs.



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